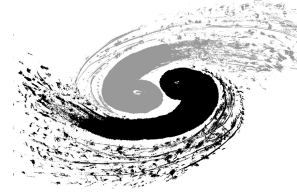


Sensor Simulation Update



中國科學院高能物理研究所
Institute of High Energy Physics
Chinese Academy of Sciences

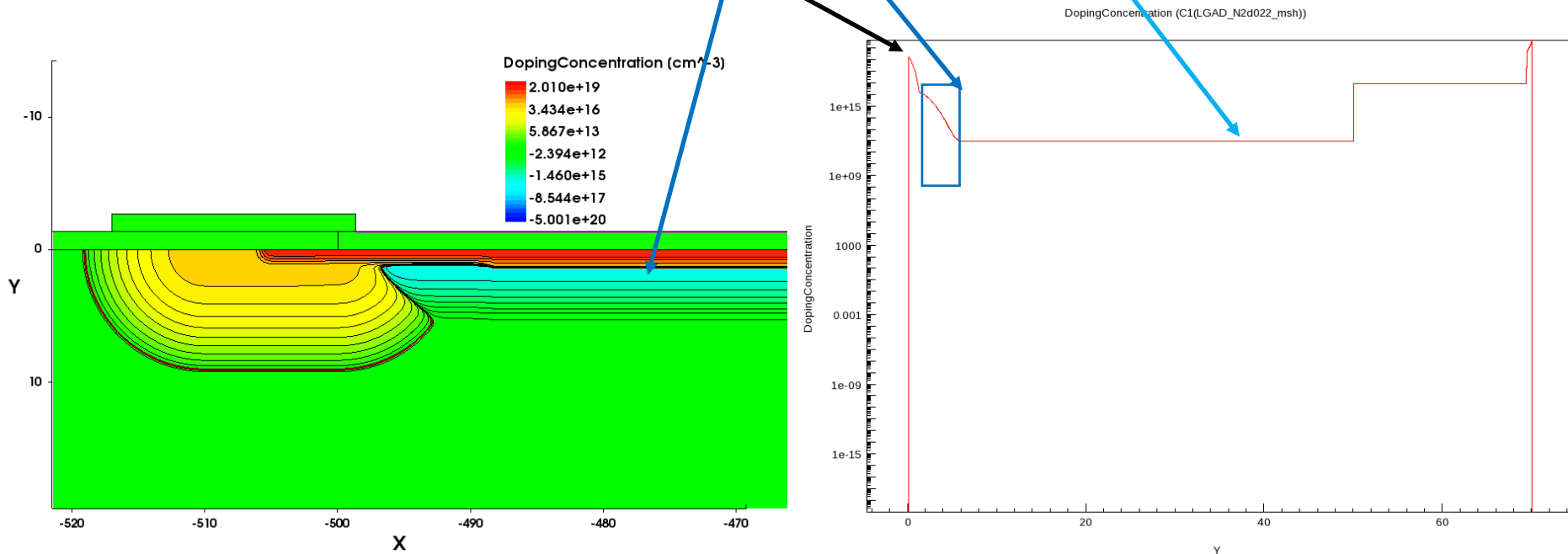
WU Kewei
2019/03/21

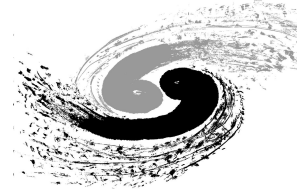


IHEP Baseline Doping Profile

Baseline doping N++, P+, **P**, **P-** substrate

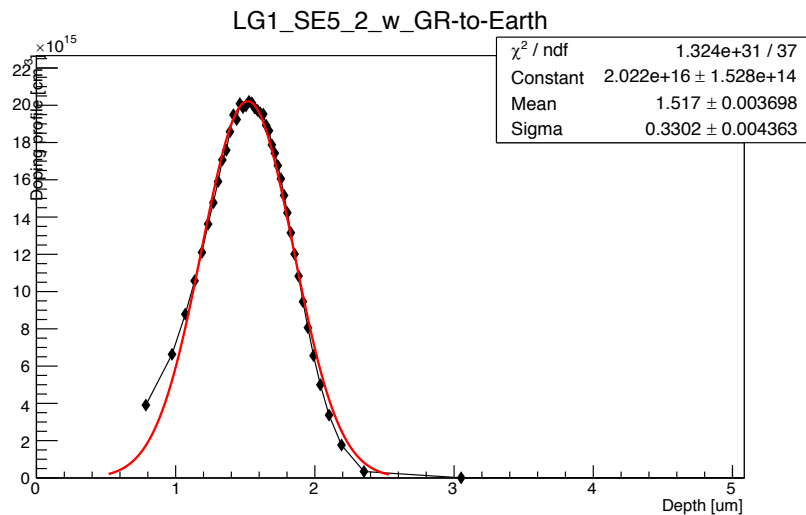
BDV = -410V, Gain@-320V = 10.45



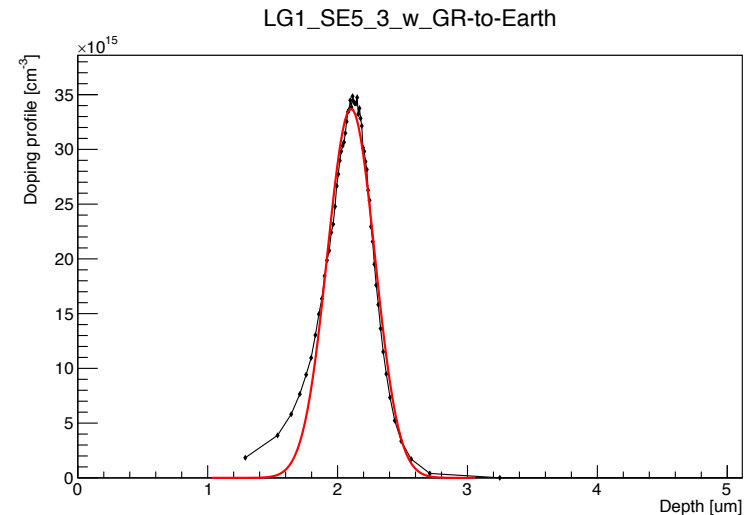


HPK Doping Profile

W8 doping profile



W18 doping profile



Single P layer **2e16**:

BDV = -417V, Gain@-320V = 2.5, Gain@-400V = ???

Single P layer **2.5e16**:

BDV = -310V, Gain@-300V = 9.9

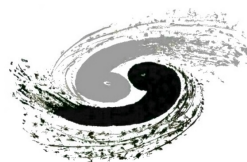
Double P layer P+ and **2e16**:

BDV = -421V, Gain@-320V = 1.6

Single P layer **3.37e16**:

BDV = -408V, Gain@-380V = 1.58

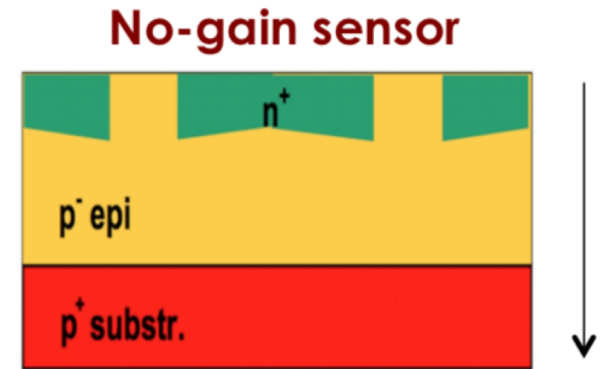
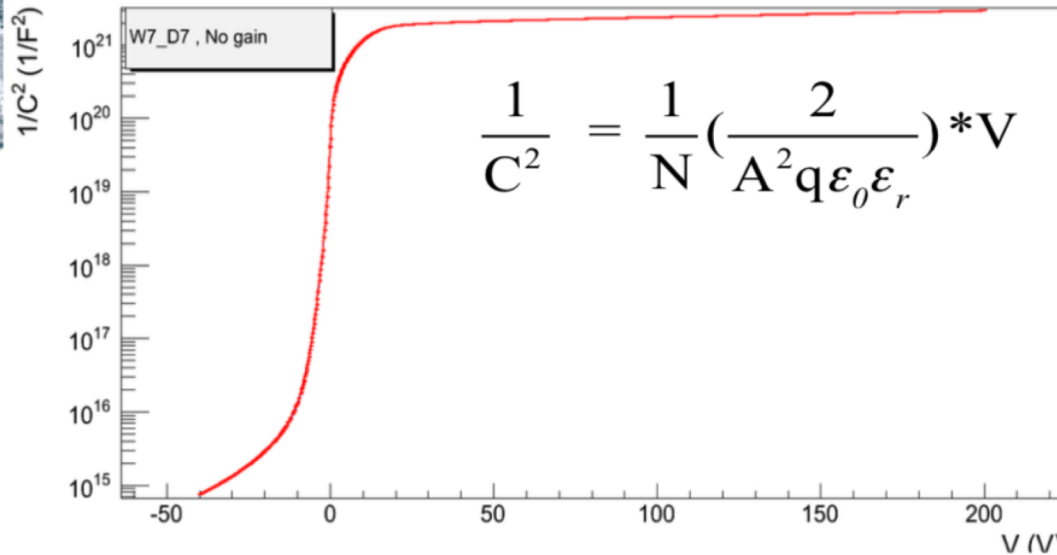
Thanks for your listening!



中國科學院高能物理研究所
Institute of High Energy Physics
Chinese Academy of Sciences

WU Kewei
2019/03/21

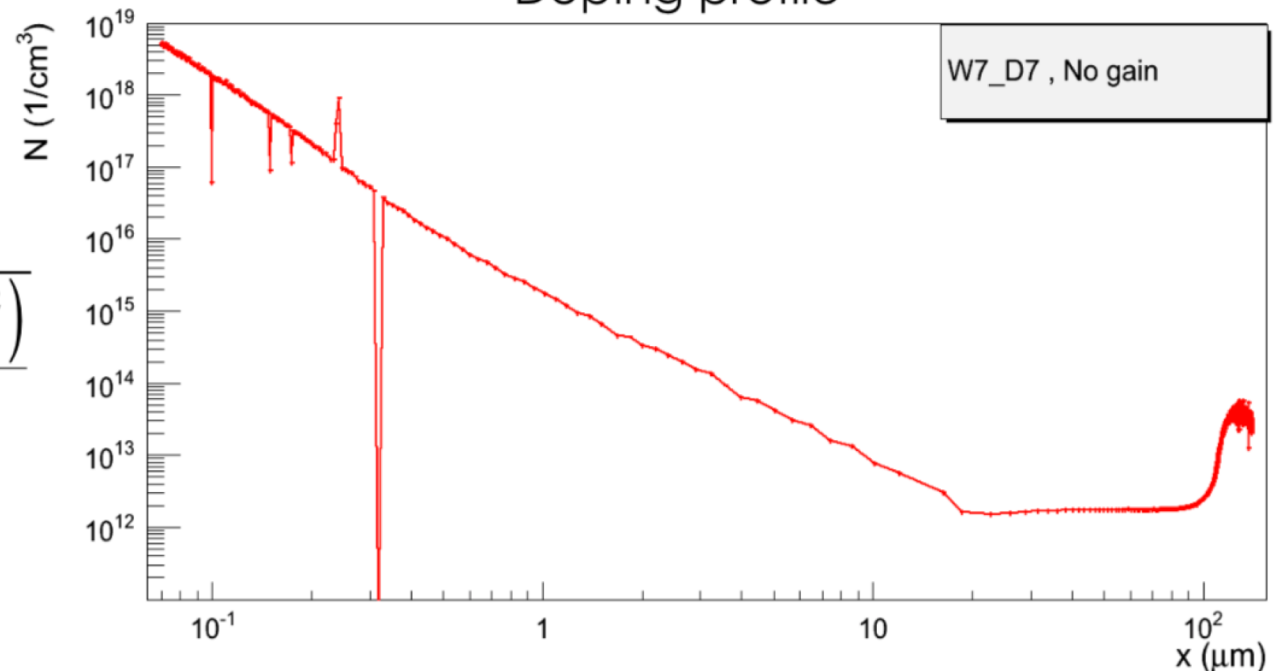
Doping profile from CV measurement - I

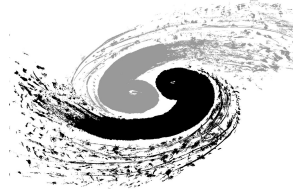


Doping profile

$$N = \frac{2}{q \epsilon_0 \epsilon_r A^2} \frac{d(1/C^2)}{dV}$$

Doping





CV Measurement

Anybody want to learn more could click the link below:

Doping->Gain:

https://indico.cern.ch/event/468478/contributions/2135146/attachments/1290321/1921375/LGA_Signal_Cartiglia.pdf

CV->Doping:

https://ecee.colorado.edu/~bart/book/book/chapter4/ch4_3.htm#fig4_3_3